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Title of Invention	Method for forming silicon dioxide film using siloxane
Application Number :	10/782094
Date :	2004-02-19
First Named Applican	: Mr. Park Jae-eun
Confirmation Number	4756
Attorney Docket Num	per: SAM-0483

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Submitted By:	Elec. Sign.	Sign. Capacity
Mr. Anthony P. Onello Jr.	/Anthony P. Onello,	Attorney
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Documents being submitted:	Files
us-ids	SamsungFourEightyThreePartThree-usidst.xml us-ids.dtd
	us-ids.xsl
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